

Nanopatterning of Co₇₃Pt₂₇-TiO₂ magnetic thin film by focused ion beam irradiation

김성동[†], 박진주^{*}

서울산업대학교 기계설계자동화공학부; *서울테크노파크
(sdkim@snut.ac.kr[†])

Nano-scale fabrication becomes an essential process in various application fields of magnetic thin films such as MRAM, patterned media and spintronic device. The topographic patterning process, for example, IBE(ion beam etching) and RIE(reactive ion etching), fabricates the nano-structure by removing the unnecessary materials and inherently has drawbacks like etching damage, redeposition and planarity issue. Recently, there has been an attempt to avoid these setbacks by applying non-topographic patterning process for magnetic thin films. This pure magnetic patterning technology utilizes the irradiation or implantation of ions like He⁺, Ga⁺, Ni⁺ into the magnetic thin films in order to modify the magnetic properties. When Ga⁺ ions are irradiated with FIB(focused ion beam) system, it is possible to fabricate the magnetic thin films directly in nano-scale with the combination of the irradiation induced magnetic patterning and the direct nano-fabrication ability of FIB. In this presentation, we will show their radiation effects of Ga⁺ ion on the magnetic properties of perpendicular magnetic recording media for DTR (discrete track recording) and patterned media applications. The perpendicular media was prepared on a glass substrate and its detailed structure was Glass/Ta 5 nm/CoFeZrNb 40 nm/Ta 3 nm/Ru 15 nm/Ru-O₂ 8 nm/Co₇₃Pt₂₇-TiO₂ 16 nm. The sample was then exposed to the 10 pA 30 keV Ga⁺ focused ion beam with different dose from 1×10^{15} ions/cm² to 30×10^{15} ions/cm². The exposed area was $3 \times 3 \mu\text{m}^2$ and the change of magnetic properties were observed with the MFM(magnetic force microscopy). As Ga⁺ ion dose increased from 1×10^{15} ions/cm² to 30×10^{15} ions/cm², the perpendicular magnetic anisotropy was degraded and no longer observed above 20×10^{15} ions/cm² dose. The deterioration of the perpendicular magnetic anisotropy and ferromagnetic properties can be attributed to the concentration profile change due to Ga⁺ ion implantation.

Keywords: FIB, magnetic, nanopattern

TiO₂ Nanocarving Process:

Selective and Anisotropic Nanosized-Etching of Bulk TiO₂ into Nanofibers

유세훈[†]

한국생산기술연구원
(yoos@kitech.re.kr[†])

The widespread utilization of nano-structured materials is often complicated by the conflicting demands for precise control of fine features (down to the nanometer scale) and for large-scale mass production. Recently, a simple, inexpensive gas phase reaction termed as “nanocarving process” has been developed for TiO₂ single crystal nanofibers. The nanocarving process converts TiO₂ grains into arrays of single crystal nanofibers by selective and anisotropic etching. Unlike other nano-structure forming techniques, nano-carving doesn't require any sophisticated equipment. All one needs to produce the structure is a controlled atmosphere furnace for a subsequent heat treatment (5% H₂/N₂ at 700 °C). This process yields high surface area structures that are well attached to a substrate making them easy to adapt for industrial and commercial applications. This presentation reviews the condition for the nanocarving process and discusses the mechanism of the selective etching

Keywords: TiO₂, Nanofiber, Nanowire, Synthesis, Etching